Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	46246	(adhe\$5 or bond\$4 or contact\$4) near4 (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:28
L2	853953	I1 and master or matrix	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:28
L3	7312	I1 and (master or matrix)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/18 10:29
L4	232	I3 and (HMDS or TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:30
L5	251911	("10" or "20" or "30" or "40" or "50" or "45" or "35" or "25" or "15") adj4 (nm or nanometers)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:46
L6	117	I4 and I5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:32
L7	52	I6 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:35

L8	736	428/405.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:35
L9	565	l8 and @ad<"20021029"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:35
L10	565	l8 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:35
L11	27	l10 and (primer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:36
L12	0	l11 and (HMDS or TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:36
L13	12	I10 and (HMDS or TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:37
L14	1097	(HMDS or TMSDEA) with (substrate or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:37

L15	30	I14 with (nm or nanometers)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:37
L16	· 17	l15 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:44
L17	1	"5093153".pn. and (resist or photoresist or polymer or resin or photopolymer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:45
L18	31905	(adhe\$5) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:46
L19		I18 with I5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:46
L20	37	I19 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:49
L21	1165	silane with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/18 10:49

L22	1011	silane with I5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:50
L23	27	l21 and l22	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:50
L24	25	I23 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:54
L25	52	HMDS with (("30" or "40") adj4 (nm or nanometers))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:55
L26	16	l25 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:57
L27	54	(particle adj2 size) with HMDS	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF .	2007/12/18 10:57

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S19 4	32	S193 with water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:20
S19 5	186672	adhesive adj2 layer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:21
S19 6	33714	S195 with substrate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:22
S19 7	9	S196 with rinsing	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:24
S19 8	5168	rins\$4 with ("30" adj2 second\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:25
S19 9	649	S198 with (remov\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:25
S20 0	328	S199 and excess	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:26

S20 1	11	S200 and S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:28
S20 2	420065	(rins\$4 or wash\$4) with remov\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:29
S20 3	586	S202 same ((control\$4 or manipulat\$4) near4 (depth or thickness))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:29
\$20 4	213	S203 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:45
\$20 5	0	S204 and S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:30
S20 6	15735	(HMDS or TMSDEA or hexamethyldisilazane or trimethylsilyldiethylamine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:31
S20 7	0	S205 and S206	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:31

S20 8	0	S204 and S206	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:32
S20 9	64	(HMDS and TMSDEA) or (hexamthyldisilazane and trimethylsilyldiethylamine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:33
S21 0	11	S209 and (master or matrix)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:33
S21 1	248115	(silyl\$4 or silan\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:33
S21 2	28885	S211 with (substrate or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:34
S21 3	57065	(rins\$4 or wash\$4) with (("1" or "2" or "3" or "4" or "5" or one or two or three or four or five or "10" or "20" or "30") adj4 (seconds or second or S or sec))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:39
S21 4	157099	(substrate or base) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:45

S21 5	149	S113 and S114	US-PGPUB; USPAT;	OR	OFF	2007/12/17 17:49
)			USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB			
S21 6	88	S215 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:49
S21 7	2468	S213 and S214	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:49
S21 8	1457	S217 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:00
S21 9	39267	(adhesion or bonding or bond or bonded or adhered or adhere or adhesive) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:51
S22 0	562	S218 and S219	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:52
S22 1	343040	(remove or removal or removed) with (contact or adhesive or adhesion or silame or S79)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:53

S22 2	. 107	S221 and S220	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:59
S22 3	735	(428/405).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:00
S22 4	339	S223 and (rins\$4 or wash\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 5	278	S224 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 6	15	S225 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 7	565	S223 and (rins\$4 or wash\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 8	453	S227 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07

S22 9	36	S228 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:08
S23 0	21	S229 not S226	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:10
S23 1	1789	(substrate or base) same (HMDS or TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:11
S23 2	522	S231 same remov\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:11
S23 3	29	S232 same excess	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:15
S23 4	43178	(resist or photoresist) same (HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:18
S23 5	6374	(HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer))) with S149	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:20

S23 6	1353	S234 and S235	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:19
S23 7	1353	S236 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:19
S23 8	30153	(HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer))) near3 (rins\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:24
S23 9	3267	S238 same (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:25
S24 0	216	S239 same water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:29
S24 1	117	S240 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:02
S24 2	3	"3692092".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:51

S24 3	3	"3867175".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:51
S24 4	14	"4272601"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:51
S24 5	2	"4272601".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:59
S24 6	529329	(adhesive or adhesion or contact or bonding or bond or HMDS or TMSDEA) adj3 (film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:00
S24 7	430472	(rins\$4 or wash\$4 or remov\$4) with (excess or dirt or impurities)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:01
S24 8	26695	S246 and S247	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:01
S24 9	3573	S246 same S247	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:02

S25 0	1010	S249 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:02
S25 1	459	S250 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04
S25 2	910	S249 same water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04
S25 3	206	S252 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04
S25 4	62	S253 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:20
S25 5	287	HMDS.cim.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:20
S25 6	10	S255 and rins\$4.clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:26

S25 7	2756	(rinse or wash or remove) with (primer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:26
S25 8	31	S257 same (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:24

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S25	1	"5783371".pn. and (metal\$4 near2 substrate)	US-PGPUB; USPAT	OR	OFF	2007/12/12 10:42
S6	1	"6866927".pn.	US-PGPUB; USPAT	OR	OFF	2007/12/10 08:17
S55	216429	\$10silane	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 12:24
S18 6	976	( substrate) with S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:09
S14 9	251347	("10" or "15" or "20" or "25" or "30" or "35" or "40" or "45" or "50" or "55" or "60") adj3 (nm or nanometers)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/17 15:22
S96	31259	("30" or thirty) with (rinse or rinsing or rinsed)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:49
S11 6	0	("3645772" and "3629036").pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:42
S11 7	0	("3645772".pn. and "3629036".pn.)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:43

S41	123	(((test or trial) adj2 (area or region)) same overlap)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:08
S16 9	500312	((bond\$3 or contact\$4 or adhe\$4) adj2 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:12
S18 8	41944	((bond\$3 or contact\$4 or adhe\$4) adj2 (film or layer)) with remov\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:13
S16 5	4525	((bond\$3 or contact\$4 or adhe\$4) adj2 (film or layer)) with S149	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:55
S74	681730	((optical or laser or information) near5 (disk or disc or media or medium))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 15:04
S67	4776	((optical or laser or information) near5 (disk or disc or media or medium)) near2 (master or matrix)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 15:04
S30	2685	(369/275.3).ccls. or (369/286).ccls.	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:53
S22 3	735	(428/405).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:00

S89	6851	(adhe\$5 near2 (film or layer)) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:55
S15 2	1145	(adhesion adj2 (film or layer)) with S149	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:27
S21 9	39267	(adhesion or bonding or bond or bonded or adhered or adhere or adhesive) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:51
S24 6	529329	(adhesive or adhesion or contact or bonding or bond or HMDS or TMSDEA) adj3 (film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:00
S66	42773	(bond or bonding or adhesion or adhere or adhesive or bound) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 14:58
S16 2	500312	(bond\$3 or contact\$4 or adhe\$4) adj2 (film or layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:50
S59	41785	(bonding or bond or adhesion or adhere or adhesive) with (resist or photoresist or photosensitve)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 12:32

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S17 3	304582	(control\$4 or manipulat\$4) with (depth or thickness or thick)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:01
S17 5	123	(glass adj substrate) same HMDS	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:04
S17 8	2045	(glass adj substrate) same rins\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:06
S18 3	0	(glass adj substrate) with (TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:08
S17 6	63	(glass adj substrate) with HMDS	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:06
S18 0	854	(glass adj substrate) with rins\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:08
S18 4	76	(glass adj substrate) with S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:09

		(1)	LIC BOST IS	00	055	2007/42/47 46 55
S20 9	64	(HMDS and TMSDEA) or (hexamthyldisilazane and trimethylsilyldiethylamine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:33
S20 6	15735	(HMDS or TMSDEA or hexamethyldisilazane or trimethylsilyldiethylamine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:31
S13 0	32	(HMDS or TMSDEA or hexamethyldisilazane or trimethylsilyldiethylamine) and S126	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:31
S87	8	(HMDS or TMSDEA or hexamethyldisilazane or trimethylsilyldiethylamine) with ((rins\$3 or wash\$3 or dip\$3 or soak\$3) and (thickness or depth))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:14
S23 8	30153	(HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer))) near3 (rins\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:24
S23 5	6374	(HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer))) with S149	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:20
S14 8	1096	(HMDS or TMSDEA) with (substrate or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR ,	OFF	2007/12/17 15:32

S11 2	857022	(improve or increase or greater or larger or increased or improved) with ( adhesion or adhere or adhesive or contact or bonding or contacting)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:28
S35	29384	(multiple or plural or plurality or many or several or first or second or S28 or S29 or one or two or "1st" or "2nd") near3 ((recording or data or information or reproducing or reproducation or record) near2(film or layer))	US-PGPUB; USPAT	OR	OFF	2007/12/12 15:01
S29	358269	(optical or laser or information) near5 (disc or disk or media or medium)	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:52
S54	660307	(optical or laser or information) near5 (disk or disc or media or medium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 12:23
S88	660435	(optical or laser or information) near5 (disk or disc or media or medium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:55
S22 1	343040	(remove or removal or removed) with (contact or adhesive or adhesion or silame or S79)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:53
S23 4	43178	(resist or photoresist) same (HMDS or TMSDEA or trimethylsilyldiethylamine or hexamethyldisilazane or ((adhes\$4 or contact\$3 or bond\$4) near3 (film or layer)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:18

S24 7	430472	(rins\$4 or wash\$4 or remov\$4) with (excess or dirt or impurities)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:01
S21 3	57065	(rins\$4 or wash\$4) with (("1" or "2" or "3" or "4" or "5" or one or two or three or four or five or "10" or "20" or "30") adj4 (seconds or second or S or sec))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:39
\$20 2	420065	(rins\$4 or wash\$4) with remov\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:29
S13 2	357	(rins\$4 with (remov\$4 and silane))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/17 14:31
S81	37355	(rinse or rinsed or rinsing or wash or washed or washing or dip or dipped or dipping or soak or soaking or soaked) with (("1" or "2" or "3" or "4" or "5" or one or two or three or four or five) near3 (s or second or seconds))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:33
S90	5274	(rinse or rinsed or rinsing or wash or washed or washing or dip or dipped or dipping or soak or soaking or soaked) with (adhe\$5 near2 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:29
S85	193	(rinse or rinsed or rinsing or wash or washed or washing or dip or dipped or dipping or soak or soaking or soaked) with S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:31

S12 6	2296	(rinse or rinsing or rinsed) near3 (("1" or "2" or "3" or "4" or "5" or one or two or three or four or five) adj3 (s or sec or seconds or second))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2007/12/17 14:12
S25 7	2756	(rinse or wash or remove) with (primer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:26
S15 7	1331	(S79) with (substrate or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:32
S47	660	(semitransparent) with (metal\$4 adj3 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:52
S21 1	248115	(silyl\$4 or silan\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:33
S23 1	1789	(substrate or base) same (HMDS or TMSDEA)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:11
S13 3	929255	(substrate or base) with (metal or glass)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:32

S13 4	1029039	(substrate or base) with (metal\$4 or glass)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:32
S21 4	157099	(substrate or base) with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:45
S43	101608	(thin or translucent or transparent) with (metal\$4 adj3 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:52
S32	26832	(trial or test) near3 (area or region)	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:54
S14 3	190088	(wash\$4 or rins\$4) with remove	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:59
S14 2	185155	(wash\$4 or rinse\$4) with remove	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:59
S11	2405	355/77.ccls.	US-PGPUB; USPAT	OR	OFF	2007/12/10 09:11
S19 5	186672	adhesive adj2 layer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:21
S19	<b>1</b>	elini	US-PGPUB; USPAT	OR	OFF	2007/12/10 11:14
S18	0	ellini	US-PGPUB; USPAT	OR	OFF	2007/12/10 11:14

S99	0	EP-0346650-\$.did,	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:51
S10 0	0	EP-0346650-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:51
S10 1	2	EP-346650-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:52
S11 1	2	EP-667608-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:25
S69	15602	hexamethyldisilazane or HMDS or trimethysilyldiethylamine or TMSDEA	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/13 14:59
S79	13410	HMDS or TMSDEA or (trimethyl adj2 silane) or (trimethoxy adj2 silane) or (methyl adj2 silazane)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:18
S25 5	287	HMDS.clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:20

S10 3	1	JP-3248342-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:56
S11 0	1	JP-58077044-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:23
S10 2	1	JP-61153850-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:54
S56	18654974	n-(2-amino-ethyl)-3-aminopropyl-tri methoysilane	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 12:25
S16 0	1	NL-1007216-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:45
S15 9	1	NL-9400225-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:43
S19 8	5168	rins\$4 with ("30" adj2 second\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:25

S19 3	185	rinse with silane	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:17
S10 9	0	S107 and (wash\$4 or rins\$5 or soak\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:17
S10 8	0	S107 and rins\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:17
S12	720	S11 and ((latent or color or print) near2 (image or pattern))	US-PGPUB; USPAT	OR	OFF	2007/12/10 09:11
S12 8	517	S112 and S126	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:14
S11 3	7846	S112 with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:28
S21 5	149	S113 and S114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:49
S11 4	149	S113 and S81	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:29

S11 5	88	S114 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:52
S13	639	S12 and @ad<"20021022"	US-PGPUB; USPAT	OR	OFF	2007/12/10 09:12
S12 4	228	S123 with (s or sec or seconds)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:51
S12 5	124	S124 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:33
S12 7	7	S126 same silane	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:13
S12 9	0	S127 and S88	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:14
S14	82	S13 and lithograph\$4	US-PGPUB; USPAT	OR	OFF	2007/12/10 10:14
S13 5	248	S132 and S134	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2007/12/17 14:32

S13 6	128	S135 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:42
S13 7	127	S136 and water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:41
S13 9	212	S138 and rins\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:56
S14 1	5	S138 with rins\$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:58
S14 0	127	S139 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:01
S14 4	1430	S143 with (S79 or silane or sila\$5 or adhesion or adhesive)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:00
S14 5	446	S144 and ((metal\$3 or glass) with (substrate or base))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:00

S14 6	265	S145 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT;	OR	OFF	2007/12/17 15:23
S15 8	10	S149 with S157	IBM_TDB US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT;	OR	OFF	2007/12/17 15:41
S15 0	126	S149 with S79	IBM_TDB US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/17 15:22
S15 1	38	S150 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:27
S15 3	136	S152 and ((optical or laser or information) near5 (disc or disk or media or medium))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:27
S15 4·	63	S153 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:50
S15 5	21	S154 and (master or matrix or stamper)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:28

S15 6	22	S154 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:30
S16 3	. 367	S162 same S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:49
S16 4	176	S163 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:57
S16 7	108	S164 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:53
S16 6	1	S164 and S165	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:51
S16 8	98	S167 and (rins\$4 or wash\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:55
S17 0	43902	S169 with (rins\$4 or wash\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:56

C17	2200	S170 with (thickness or depth)	US-PGPUB;	OR	OFF	2007/12/17 15:56
S17 1	2396	5170 with (thickness of depth)	USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OK .	OH	2007/12/17 13.30
S17 2	1338	S171 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:14
S17 4	286	S172 and S173	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:04
S17 7	3	S176 same "30"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:05
S17 9	0	S176 same rins\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/17 16:06
S18 1	105	S180 same "30"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:07
S18 2	37	S181 same second\$1	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:07

		C404 (II20II 1/2	LIC DODI ID	OB	OFF	2007/12/17 16:00
S18 5	0	S184 same ("30" adj2 second\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:09
S18 7	35	S186 same ("30" adj2 second\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:11
S18 9	936	S188 with (rins\$5 or wash\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:14
S19 1	133	S189 same (thickness or depth)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF.	2007/12/17 16:14
S19 2	42	S191 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:30
S19 4	32	S193 with water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2007/12/17 16:20
S19 6	33714	S195 with substrate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:22

S19 7	9	S196 with rinsing	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:24
S19 9	649	S198 with (remov\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:25
S20 0	328	S199 and excess	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:26
S20 1	11	S200 and S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:28
S20 3	586	S202 same ((control\$4 or manipulat\$4) near4 (depth or thickness))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:29
S20. 4	213	S203 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:45
S20 8	0	S204 and S206	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:32

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S20 5	0	S204 and S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:30
S20 7	0	S205 and S206	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:31
S21 0	11	S209 and (master or matrix)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:33
S21 2	28885	S211 with (substrate or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:34
S21 7	2468	S213 and S214	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:49
S21 6	88	S215 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ÖR	OFF	2007/12/17 17:49
S21 8	1457	S217 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:00

S22 0	562	S218 and S219	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 17:52
S22 2	107	S221 and S220	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF ·	2007/12/17 17:59
S22 7	565	S223 and (rins\$4 or wash\$4 or remov\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 4	339	S223 and (rins\$4 or wash\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 5	278	S224 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 6	15	S225 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07
S22 8	453	S227 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:07

S22 9	36	S228 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:08
S23 0	21	S229 not S226	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:10
S23 2	522	S231 same remov\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:11
S23 3	29	S232 same excess	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:15
S23 6	1353	S234 and S235	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:19
S23 7	1353	S236 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 18:19
S23 9	3267	S238 same (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/17 18:25

S24 0	216	S239 same water	US-PGPUB; USPAT;	OR	OFF	2007/12/17 18:29
			USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB			
S24 1	117	S240 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OŔ	OFF	2007/12/17 19:02
S24 8	26695	S246 and S247	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:01
S24 9	3573	S246 same S247	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:02
S25 0	1010	S249 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:02
S25 2	910	S249 same water	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04
S25 1	459	S250 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04

S25 3	206	S252 and (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:04
S25 4	62	S253 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:20
S25 6	10	S255 and rins\$4.clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 19:26
S25 8	31	S257 same (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/18 10:24
S31	2453	S29 and S30	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:53
S33	196	S31 and S32	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:54
S34	117	S33 and @ad<"20040409"	US-PGPUB; USPAT	OR	OFF	2007/12/12 14:55
S36	54	S34 and S35	US-PGPUB; USPAT	OR	OFF	2007/12/12 15:24
S39	0	S36 and (((test or trial) adj2 (area or region)) with overlap)	US-PGPUB; USPAT	OR	OFF	2007/12/12 17:08
S40	0	S36 and (((test or trial) adj2 (area or region))same overlap)	US-PGPUB; USPAT	OR	OFF	2007/12/12 17:08
S38	42	S36 and ((test or trial) adj2 (recording or writing))	US-PGPUB; USPAT	OR	OFF	2007/12/12 17:07
S37	47	S36 and power	US-PGPUB; USPAT	OR	OFF	2007/12/12 16:57

S42	16	S41 and S29	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:42
S44	7994	S43 same (reflect\$4 adj3 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:52
S45	1632	S44 and S29	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:44
S46	6	S45 and ((test or trial) adj3 (region or area))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:53
S48	155	S47 same (reflect\$4 adj3 (film or layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:53
S49	35	S48 and S29	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 18:07
S50	0	S49 and ((test or trial) adj3 (region or area))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/12 17:53

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S52	2	S51 and (lead-in)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 10:28
S57	18658111	S56 or hexamethyldisilazane or HMDS or trimethysilyldiethylamine or TMSDEA	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/12/13 14:59
S58	299853	S57 and S54	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 12:26
S61	44938	S57 with (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 12:33
S60	810	S58 and S59	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 12:32
S62	122	S60 and S61	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 12:33
S63	52	S62 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 12:34

S64	25	S63 and (master or matrix)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/12/13 13:00
S68	88	S66 and S67	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 14:59
S75	1557	S66 and S74	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 15:04
S70	10	S68 and S69	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 15:00
S71	10	S70 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 15:05
S72	3	S71 and (rinse or rinsing or wash or washing)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 15:05
S73	7	S71 not S72	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 15:02

S76	113	S75 and S69	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 15:04
S77	45	S76 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/13 15:05
S78	25	S77 and (rinse or rinsing or wash or washing)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:11
S80	2067	S79 same (resist or photoresist)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:19
S82	73	S80 and S81	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:24
S84	47	S82 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:41
S86	112	S85 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 11:40

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S91	281	S89 and S90	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:35
S19 0	1180	S89 same (thickness or depth)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 16:14
594	180	S91 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:49
S93	43	S91 and lithograph\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:35
592	7	S91 and S88	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:33
S95	152	S94 not S93	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:41
S97	53	S96 with adhesive	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 12:49

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S98	21	S97 and @ad<"20021028"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:29
S12 3	4196	silane with (rinse or rinsing or wash or rinsed or washed or washing or dip or dipped or dipping or soak or soaking or soaked)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:51
S65	1	subphotoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 13:02
S13 8	976	substrate with S79	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 14:42
S17	263	vajda	US-PGPUB; USPAT	OR	OFF	2007/12/10 11:14
S16	64	verderame	US-PGPUB; USPAT	OR	OFF	2007/12/10 11:13
S10 7	1	WO-200209103-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 13:20
S16 1	2	WO-9952105-\$.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/17 15:48